

**UV and NIR dual-responsive self-assembly systems based on a
novel coumarin derivative surfactant**

Dong Wang, Xiaojun Hou, Bente Ma, Yawei Sun, Jiqian Wang*

*State Key Laboratory of Heavy Oil Processing & Centre for Bioengineering and
Biotechnology, China University of Petroleum (East China), Qingdao, 266580, China*

Supporting Information

China University of Petroleum (East China)

CORRESPONDING AUTHOR E-mail: jqwang@upc.edu.cn

Synthetic route was followed as the patent in reference 1. PAS purity analysis as follow:

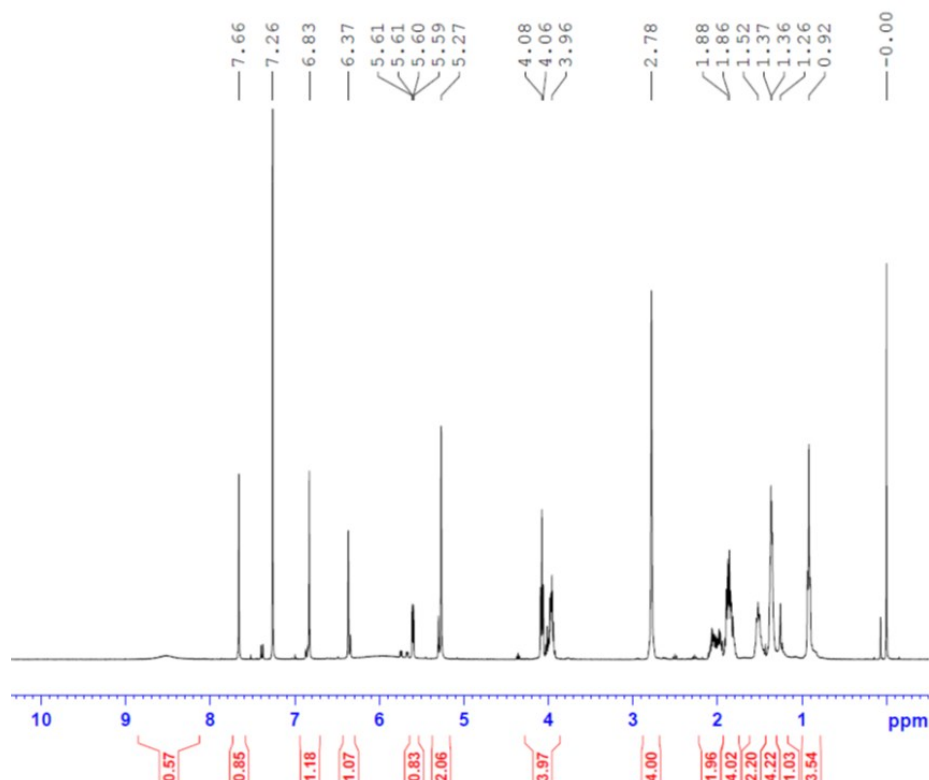


Figure S1. ^1H -NMR (CDCl_3 , 400 MHz): δ = 0.92 (s, CH_3 , 3H), 1.26-1.34 (m, CH_2 , 2H) 1.50-1.53 (m, CH_2 , 2H), 1.86-1.88 (m, CH_2 , 2H), 2.78-2.81 (m, OCH_2 , 4H), 4.06-4.09 (m, CH_2O , 2H), 5.27-5.30 (m, ArCH_2O , 2H), 6.36 (m, ArH , 1H), 6.83 (m, ArH , 1H), 7.66-7.67 (m, ArH , 1H).

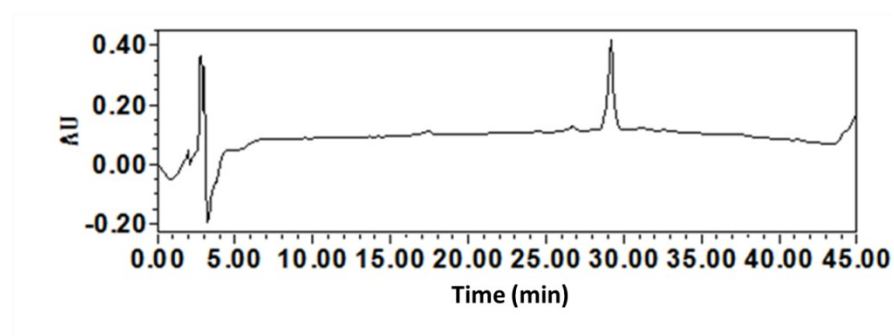


Figure S2. HPLC of PAS, the purity > 95%.

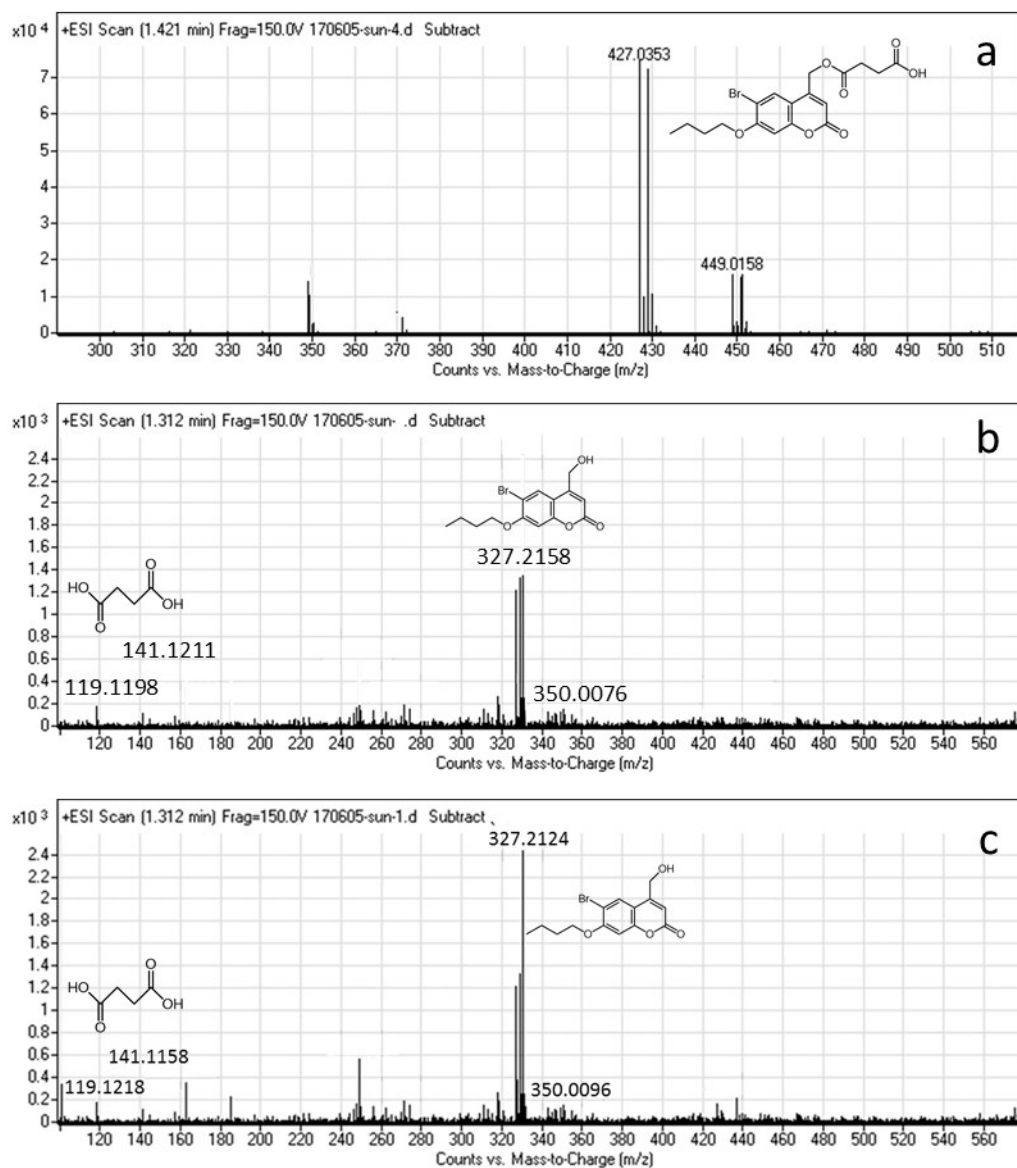


Figure S3. MS of PAS-Na (a), PAS-Na after UV irradiation (b) and PAS-Na after NIR irradiation (c).

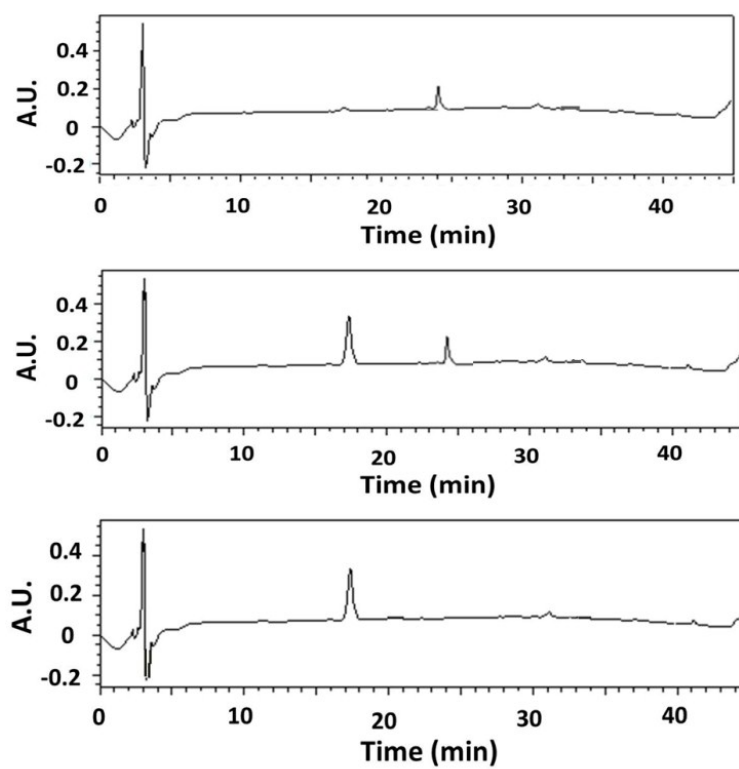


Figure S4. HPLC of 3 mmol·L⁻¹ PAS-Na undergoing UV irradiation. From top to bottom the irradiation time is 0, 1 and 3 minutes.

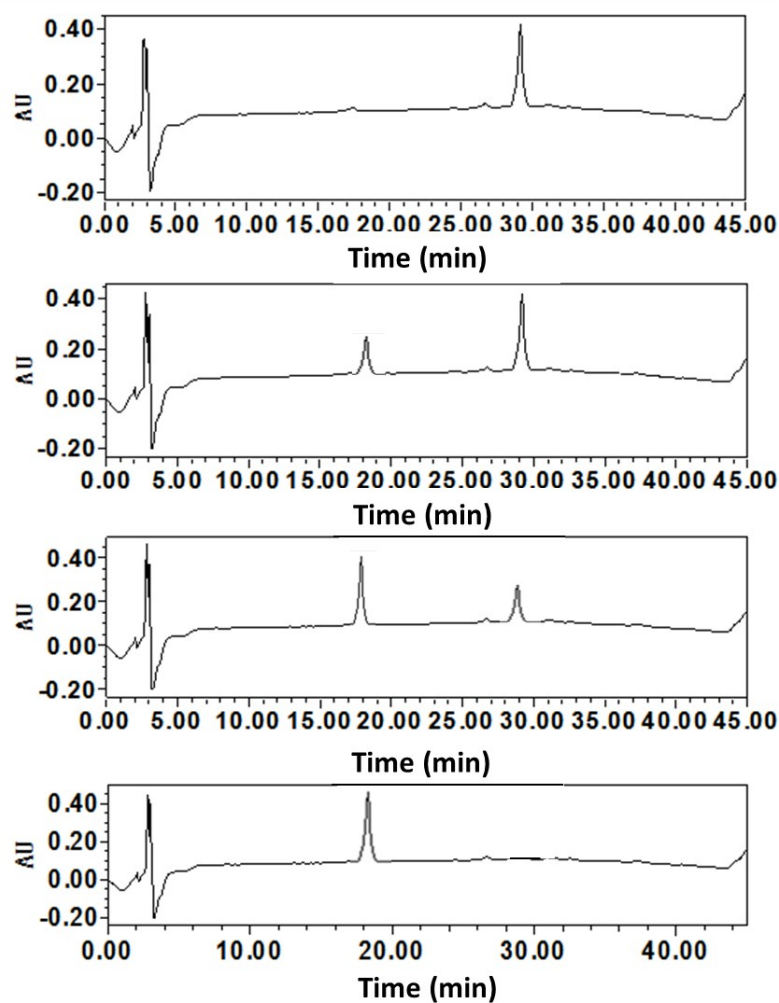


Figure S5. HPLC of 3 mmol·L⁻¹ PAS-Na undergoing NIR irradiation. From top to bottom the irradiation time is 0, 10, 30 and 45 minutes.

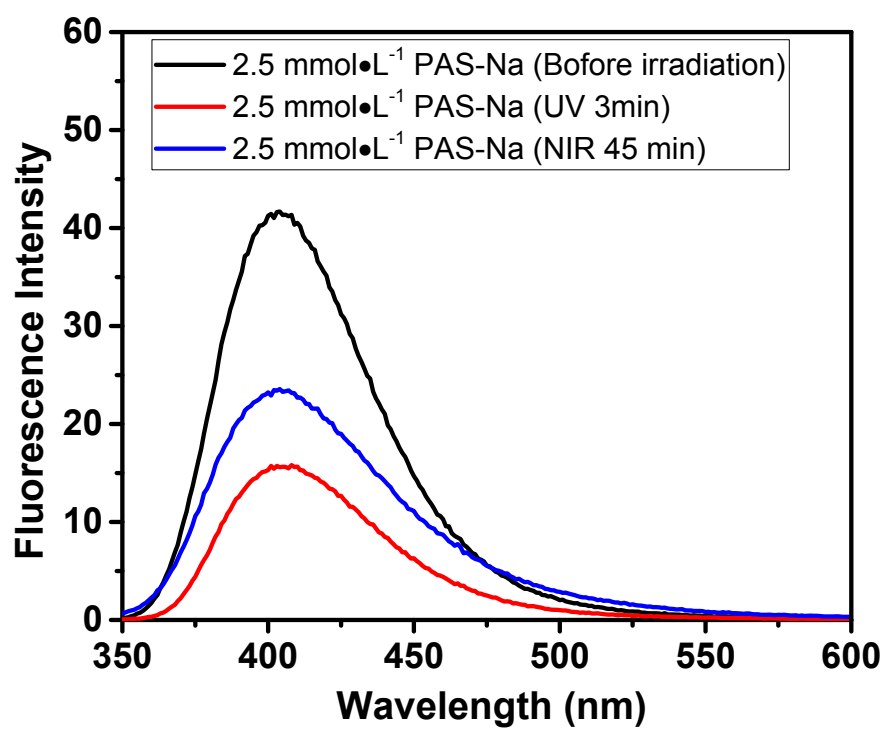


Figure S6. Fluorescence spectrum of PAS-Na before and after UV or NIR irradiation.

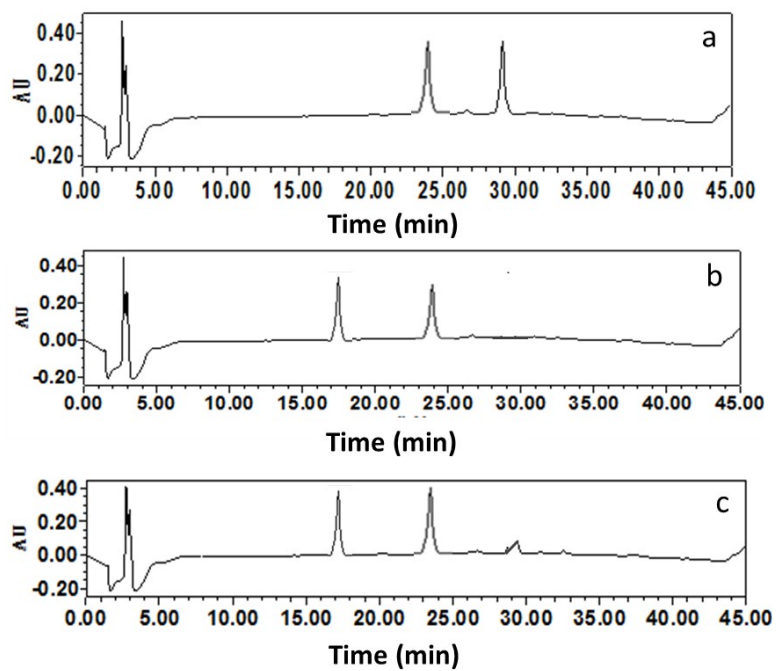


Figure S7. HPLC of $150 \text{ mmol} \cdot \text{L}^{-1}$ C_{14}DMAO with $30 \text{ mmol} \cdot \text{L}^{-1}$ PAS (a), after 10 minutes UV irradiation (b) and after 1 hour NIR irradiation (c).

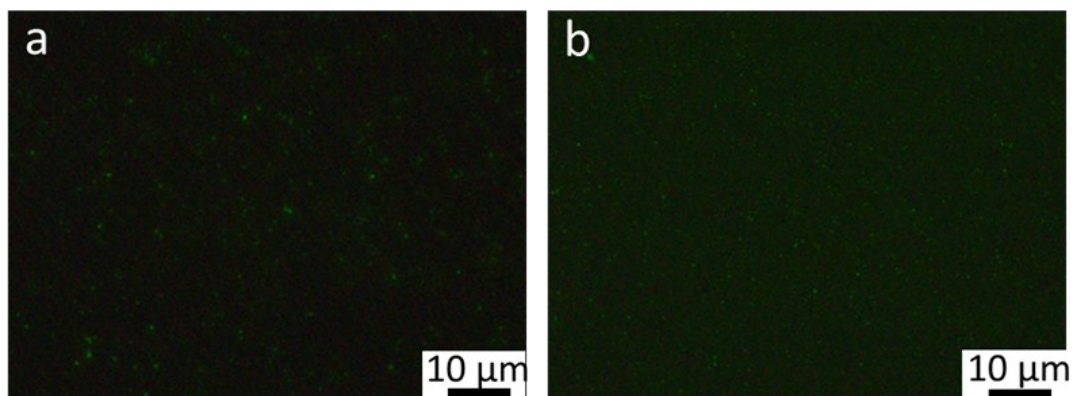


Figure S8. Fluorescence microscope images of 150 mmol·L⁻¹ C₁₄DMAO with 30 mmol·L⁻¹ PAS (a) and 150 mmol·L⁻¹ C₁₄DMAO with 50 mmol·L⁻¹ PAS (b).

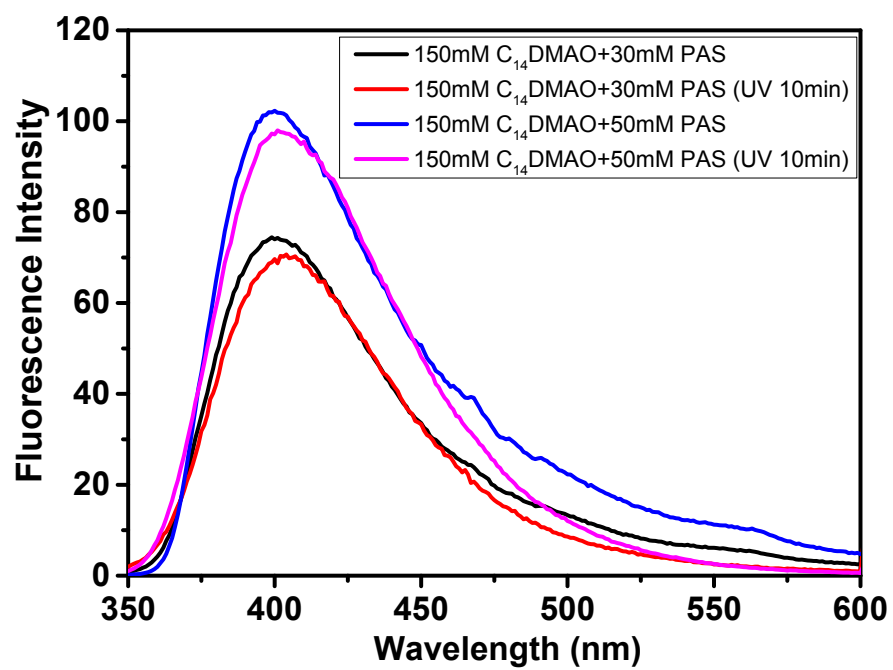


Figure S9. Fluorescence spectrum of C₁₄DMAO/PAS mixed system before and after UV irradiation.

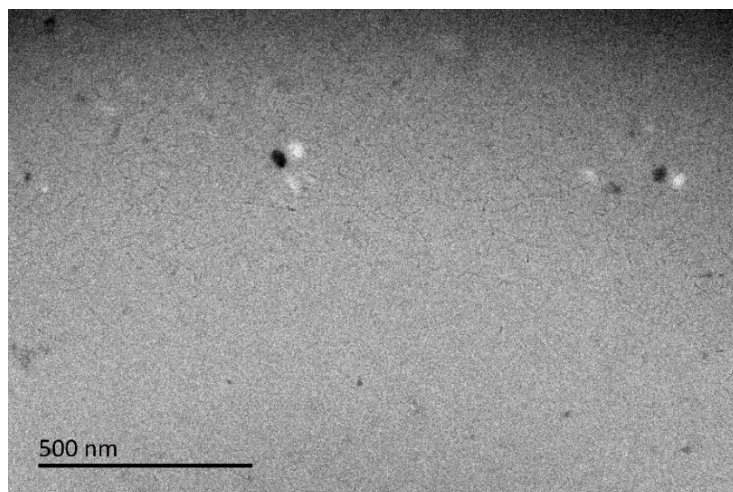


Figure S10. Cryo-TEM image of $150 \text{ mmol} \cdot \text{L}^{-1}$ C_{14}DMAO with $50 \text{ mmol} \cdot \text{L}^{-1}$ succinic acid.

References:

1. J. Wang, M. Cao, H. Yu, Y. Yan and Y. Sun, China Patent ZL201510163606.1.